## **Supplementary Information**

## A DFT-NEGF study on the electronic and transport properties of 2D SbSiTe<sub>3</sub>

Xuemin Hu<sup>a</sup>, Hengze Qu<sup>b</sup>, Lili Xu<sup>b</sup>, Wenqiang Liu<sup>b</sup>, Tingting Guo<sup>b</sup>, Bo Cai<sup>b</sup>, Xuechao Yu<sup>b</sup>, Junwu Zhu<sup>\*a</sup>, Shengli Zhang<sup>\*b</sup>

<sup>a</sup>Key Laboratory for Soft Chemistry and Functional Materials, Ministry of Education, Nanjing University of Science and Technology, Nanjing 210094, China.
E-mail: <u>zhujw@njust.edu.cn</u>

<sup>b</sup>MIIT Key Laboratory of Advanced Display Materials and Devices, School of Materials Science and Engineering, Nanjing University of Science and Technology, Nanjing 210094, China.

E-mail: <a href="mailto:zhangslvip@njust.edu.cn">zhangslvip@njust.edu.cn</a>

Туре	Lattice parameters (Å)	L (Å)	d <sub>0</sub> (Å)
Bulk	a=b=7.147	3.953	3.161
Five-layer	a=b=7.141	3.956	3.168
Four-layer	a=b=7.139	3.958	3.169
Trilayer	a=b=7.138	3.959	3.175
Bilayer	a=b=7.133	3.963	3.175
Monolayer	a=b=7.127	3.973	/

**Table S1.** The optimized lattice parameters, layered thickness (L), and interlayer distance  $(d_0)$  for few-layer SbSiTe<sub>3</sub>.

Туре	<b>Binding Energy (eV/atom)</b>
Bulk	4.210
Five-layer	4.191
Four-layer	4.186
Trilayer	4.178
Bilayer	4.162
Monolayer	4.118

Table S2. The binding energy of few-layer and bulk SbSiTe<sub>3</sub>.

**Table S3.** The off-current ( $I_{off}$ ) and the on-current ( $I_{on}$ ) of 2D SbSiTe<sub>3</sub> MOSFET with the channel length is 10 nm and 5nm.

Туре	Channel length (nm)	V <sub>dd</sub>	I <sub>off</sub> (μΑ/μm)	I <sub>on</sub> (μA/μm)
	10	0.72	0.1	210
		0.72	2×10 <sup>-5</sup>	30

	5	0.64	0.1	51
	3	0.64	5×10 <sup>-5</sup>	\
n-type				
	10	0.72	0.1	350
,	10	0.72	2×10 <sup>-5</sup>	32
р-туре	-	0.64	0.1	223
	5	0.64	5×10 <sup>-5</sup>	\



Fig. S1. The band structure of bulk SbSiTe<sub>3</sub> at HSE06 level.



Fig. S2. The band structure of bulk SbSiTe<sub>3</sub> at HSE06+soc level.



**Fig. S3**. The phonon spectrums of (a) monolayer, (b) bilayer and (c) bulk SbSiTe<sub>3</sub>. (d) The total energy variation versus time at T = 300 K, and insert is the top and side views of a snapshot of monolayer SbSiTe<sub>3</sub> after 3 ps in the MD simulation.



Fig. S4. The band structures of (a) four-layer and (b) five-layer SbSiTe<sub>3</sub> at PBE level.



**Fig. S5**. The band structure of monolayer SbSiTe<sub>3</sub> at (a) PBE + soc, (b) HSE06 and (c) HSE + soc level.



**Fig. S6.** (a) The energy-strain relation and the energy shifts versus strain with respect to the vacuum energy of (b) CBM and (c) CBM for monolayer SbSiTe<sub>3</sub>.